

### **Amendments to the Abstract**

***Please amend the Abstract of the Disclosure as follows:***

A chemical vapor deposition (CVD) ~~method~~ apparatus for depositing a silicide and a CVD system for performing the same are is disclosed. After a substrate is loaded in a load-lock chamber, the substrate is transferred into a processing chamber. A silicide is deposited on ~~[[a]]~~ the substrate. After the substrate is transferred into the load-lock chamber, ~~Residual~~ residual gases remaining ~~from the depositing step on the substrate~~ are purged out by flowing air including H<sub>2</sub>O (g) from an air purge line connected to the load-lock chamber. ~~to substantially remove fumes caused by the residual gases.~~ The purged residual gases are exhausted by a vacuum pump connected to the air purge line. ~~In the purge step, the cycle purge is carried out at the conditions similar to the flow of atmosphere, to substantially remove the fumes.~~